



Nanostructure growth, characterization and applications

Control and characterization of self-assembled Ge quantum dots grown by pulsed laser deposition

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Abstract

- Growth dynamics and morphology of self-assembled Ge QD on Si(100)-(2x1) by nanosecond PLD
- *In situ* RHEED and post deposition AFM
- Effects of laser fluence and substrate temperature on QD
- 3x laser fluence $\rightarrow 20x$ QD density & 0.3x average size

 \rightarrow shape: large huts \rightarrow domes

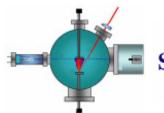
• Temperature effect:

150 °C: misaligned QDs

400 °C & 500 °C: oriented huts and domes

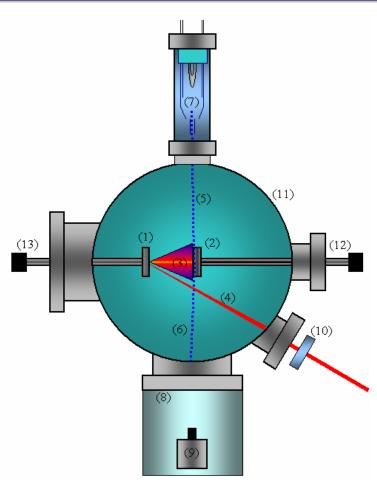
600 °C: QDs on textured surfaces





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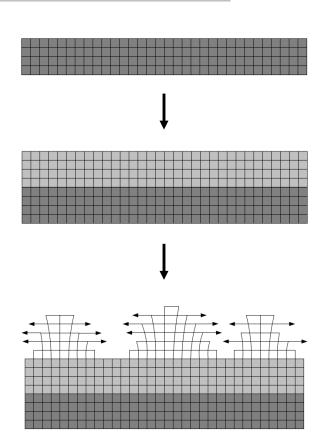
Pulsed Laser Deposition (PLD)



- (1) Target
- (2) Substrate
- (3) Ablated species "Plume"
- (4) Focused laser
- (5) Electron probe
- (6) Diffracted electrons
- (7) Electron gun
- (8) Phosphor screen
- (9) CCD camera
- (10) Focusing lens
- (11) Ultrahigh vacuum chamber
- (12) Substrate manipulator
- (13) Target manipulator

Self-assembly of Ge QDs on Si(100)-2x1

- Stranski-Krastanow (SK) growth in lattice-mismatched systems
- Epitaxial layer first formed
- Strain increases with film thickness
- At critical thickness → 3D relieves strain
- Hut clusters first form
- Huts → domes with growth

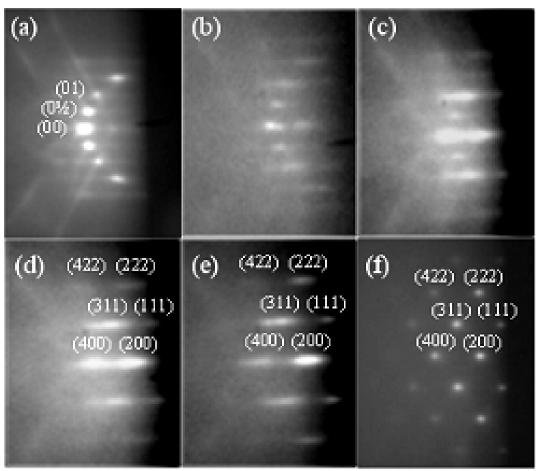


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I. Ge QD growth dynamics by PLD

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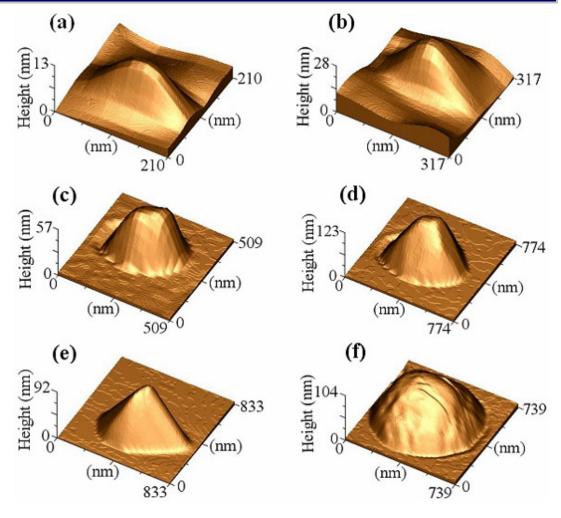
RHEED monitors growth dynamics



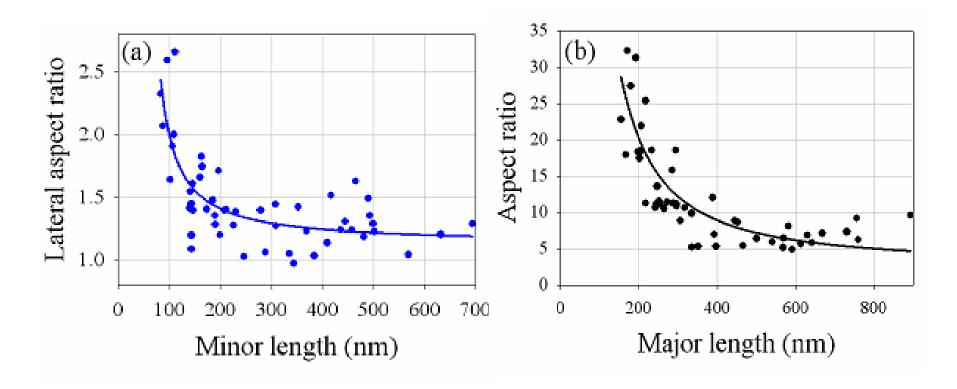
Deposition at 400 °C, 23 J/cm2, 10 Hz. (a) (2×1) substrate, (b) ~3.3 ML, (c) ~4.1 ML, (d) ~6 ML, (e) ~9.3 ML, and (f) ~13 ML

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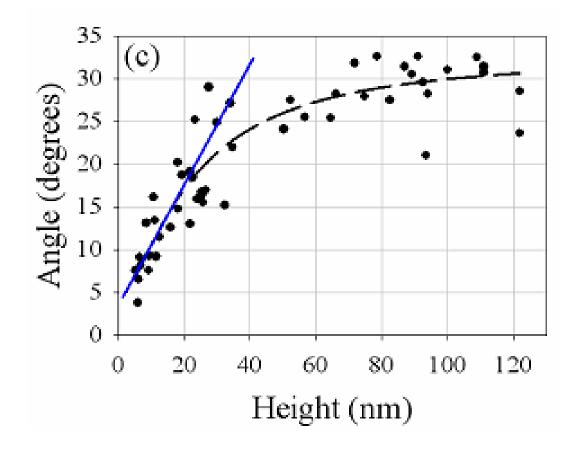
Morphology studied by ex-situ AFM



QD lateral and height aspect ratios



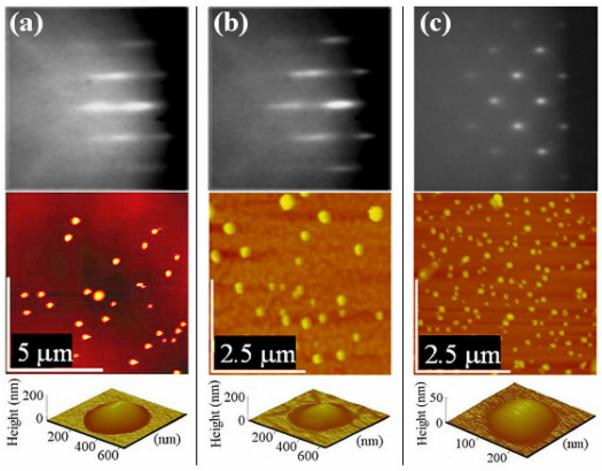
Variation of contact angle with QD height



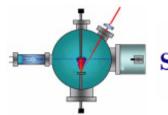
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II. Effect of laser fluence

Shape, size and density change with fluence

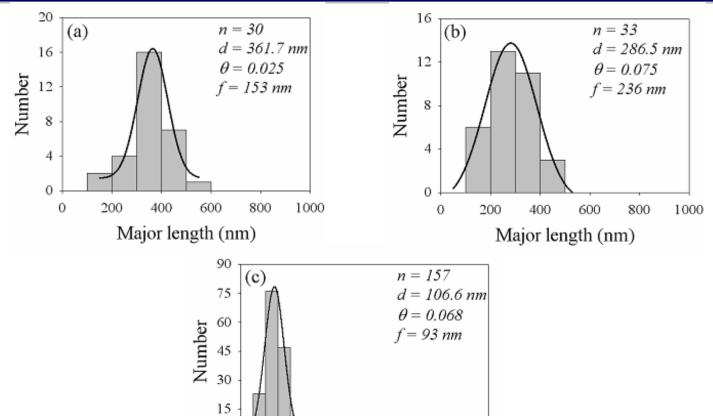


Deposition parameters: 400 °C, 10 Hz and column (a) 23 J/cm2, column (b) 47 J/cm2, column (c) 70 J/cm2



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Shape, size and density change with fluence



400

200

0

Major length (nm) 400 °C, 10 Hz and column (a) 23 J/cm², column (b) 47 J/cm², column (c) 70 J/cm²

800

1000

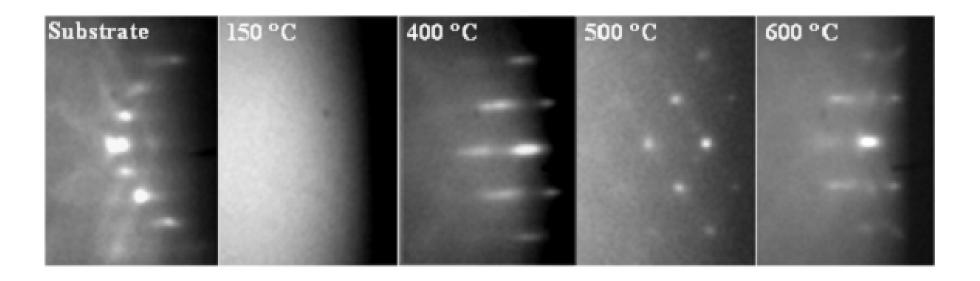
600

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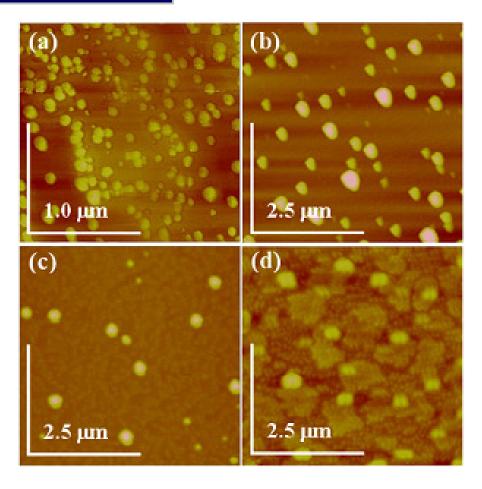
III. Effect of temperature

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RHEED detection of temperature effect



Temperature effect



(a) 150 °C, (b) 400 °C, (c) 500 °C, (d) 600 °C

Summary

- Growth dynamics of PLD of Ge QDs on Si(100)-(2x1) was studied by RHEED and AFM
- When the laser fluence is tripled, the QD density increased ~20 times, while the average lateral size decreased >3.5 times
- The shape also changed from large huts, observed at 23 J/cm², to domes observed at the highest fluence
- At 150 °C, misaligned QDs formed resulting in diffused RHEED pattern. At 400 °C and 500 °C, transmission RHEED patterns were observed indicating the growth of oriented hut and dome QDs. Around 600 °C, the QDs were formed on top of some textured surfaces

For detailed information

- 1. M. S. Hegazy and H. E. Elsayed-Ali, "Growth of Ge quantum dots on Si by pulsed laser deposition," J. Appl. Phys. 99, 53408 (2006) [Selected to appear on the Virtual Journal of Nanoscience and Technology, Vol. 13(11) (2006)].
- 2. M. S. Hegazy and H. E. Elsayed-Ali, "Self-assembly of Ge quantum dots on **Si(100)** by pulsed laser deposition," Appl. Phys. Lett. **86**, 243204 (2005) [Selected to appear on the Virtual Journal of Nanoscience and Technology, Vol. 11, Issue 24, 2005].
- 3. M. S. Hegazy, T. R. Refaat, M. N. Abedin, H. E. Elsayed-Ali, "Fabrication of GeSi quantum dot infrared photodetector by pulsed laser deposition," Optical Eng. Lett., **44(5)**, 59702 (2005)
- 4. M. S. Hegazy and H. E. Elsayed-Ali, "Quantum-dot infrared photodetector fabrication by pulsed laser deposition technique," J. Laser Micro/Nanoengineering, in press.